

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	191793	(substrate or wafer) near4 (move or moving or moved or moves or transfer\$5 or transport\$5 or handl\$3 or convey\$5)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/01/03 15:38
L2	3826	1 with ((load adj lock) or load-lock or chamber or arm) with (environment or pressure)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/01/03 15:39
L3	92550	(project\$3 or expos\$5) near3 (chamber or station)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/01/03 15:55
L4	433535	(pre-process\$3 or process\$3 or align\$5 or (heat\$3 or thermal)) near3 (substrate or wafer)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/01/03 16:40
L5	2284	3 same 4	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/01/03 16:41
L6	273	2 and 5	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/01/03 16:41
L7	91	6 and (vacuum\$4 with (project\$3 or expos\$5))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/01/03 16:42

PK
113106

Interference Search

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	191793	(substrate or wafer) near4 (move or moving or moved or moves or transfer\$5 or transport\$5 or handl\$3 or convey\$5)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/01/03 16:57
L2	3826	1 with ((load adj lock) or load-lock or chamber or arm) with (environment or pressure)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/01/03 15:39
L3	92550	(project\$3 or expos\$5) near3 (chamber or station)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/01/03 15:55
L4	433535	(pre-process\$3 or process\$3 or align\$5 or (heat\$3 or thermal)) near3 (substrate or wafer)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/01/03 16:40
L5	2284	3 same 4	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/01/03 16:41
L6	273	2 and 5	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/01/03 16:41
L7	91	6 and (vacuum\$4 with (project\$3 or expos\$5))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/01/03 16:56
L8	35	6 and (vacuum\$4 with (project\$3 or expos\$5))	US-PGPUB	OR	ON	2006/01/03 16:57
L11	10	(2 and 3 and 4 and (mask or reticle or pattern\$3)).clm.	US-PGPUB	OR	ON	2006/01/03 17:00

7/13/06
2/13/06